

ABSTRACT

Lithographic Apparatus and Device Manufacturing Method.

A lithographic projection apparatus is provided with an alignment sensor comprising an electron beam source 10 for providing an electron beam 12 for impinging on an alignment marker 14 on a substrate W, and a back-scattered electron detector 16 for detecting electrons back-scattered from the alignment marker 14. The alignment sensor is independent of the projection system and projection radiation, and is an off-axis alignment sensor.

Fig. 2

